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AMENDMENTS TO THE CLAIMS

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

Listing of Claims:

- 1. (Original) An insulating film comprising a compound having a borazine skeleton in a molecular structure thereof, and having a specific dielectric constant of no greater than 2.6, a Young's modulus of 5 GPa or greater and a leak current of no greater than 1×10^{-8} A/cm².
- 2. (Original) An insulating film according to claim 1, wherein the insulating film is formed from a borazine-based resin composition with a metal impurity content of no greater than 30 ppm.
- 3. (Currently Amended) An electronic part provided with a conductive layer-formed substrate and an interlayer insulating film formed on the substrate,

wherein the interlayer insulating film is composed of an insulating film according to claim 1-or 2.

- 4. (Original) A composite insulating film comprising:
- a first insulating film comprising a siloxane resin, and
- a second insulating film formed on the first insulating film and comprising a compound having a borazine skeleton in a molecular structure thereof.

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5. (Original) A composite insulating film according to claim 4,

wherein the first insulating film is composed of a siloxane resin composition comprising a siloxane resin obtained by hydrolytic condensation of a compound represented by the following formula (1):

$$X_{n}^{1}SiX_{4-n}^{2}$$
 (1)

where

X¹ represents an H atom, an F atom, a group containing a B atom, N atom, Al atom, P atom, Si atom, Ge atom or Ti atom, or an organic group of 1 to 20 carbons,

X² represents a hydrolyzable group, and

n represents an integer of 0-2, with the proviso that when n is 2, each X^1 may be the same or different, and when n is 0-2, each X^2 may be the same or different.

6. (Currently Amended) A composite insulating film according to claim 4 of 5, wherein the compound having a borazine skeleton in a molecular structure thereof has a repeating unit represented by the following formula (2):

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$$Z^{1} = -\frac{R^{3}}{R^{4}} + \frac{R^{3}}{R^{4}} + \frac{R^{5}}{R^{4}} + \frac{R^{5}}{R^{5}} + \frac$$

where

R¹ represents alkyl, aryl, aralkyl or hydrogen,

R² represents alkyl, aryl, aralkyl or hydrogen,

R³ and R⁴ represent identical or different monovalent groups selected from among alkyl, aryl, aralkyl and hydrogen,

R⁵ represents a substituted or unsubstituted aromatic divalent group, an oxypoly (dimethylsiloxy) group or oxygen,

R⁶ represents alkyl, aryl, aralkyl or hydrogen,

a represents a positive integer, b represents 0 or a positive integer, p represents 0 or a positive integer, and q represents 0 or a positive integer.

7. (Currently Amended) An electronic part provided with a composite insulating film according to any one of claims 4 to 6claim 4,

wherein the composite insulating film is formed on a substrate.

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8. (Original) A process for production of a borazine-based resin that is a polymer having a borazine skeleton on a main chain or a side chain thereof,

wherein the process comprises:

a first step of polymerizing a B,B',B"-trialkynylborazine and a hydrosilane in the presence of a solid catalyst, and

a second step of removing the solid catalyst after completing the first step.

9. (Original) A process for production of a borazine-based resin according to claim 8,

wherein the solid catalyst is a supported catalyst comprising a catalyst supported on compound-based carrier.

10. (Original) A process for production of a borazine-based resin that is a polymer having a borazine skeleton on a main chain or a side chain thereof wherein the process comprises:

a first step of polymerizing a B,B',B"-trialkynylborazine and a hydrosilane in the presence of a metal catalyst in a polymerization solvent,

a second step of adding to the polymerization system a particulate scavenger which is insoluble in the polymerization system of the first step and adsorbs the metal component from the metal catalyst, after completion of the first step, and

a third step of filtering out the scavenger to which the metal component has been adsorbed after completion of the second step.

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11. (Currently Amended) A process for production of a borazine-based resin according to any one of claims 8 to 10 claim 8,

wherein the B,B',B"-triallcynylborazine is represented by the following formula (3):

where

R¹ represents alkyl, aryl, aralkyl or hydrogen, and R² represents alkyl, aryl, aralkyl or hydrogen.

12. A process for production of a borazine-based resin according to any one of claims 8 to 10claim 8,

wherein the hydrosilane is represented by the following formula (4):

where

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R³ and R⁴ represent identical or different monovalent groups selected from among alkyl, aryl, aralkyl and hydrogen,

R⁵ represents a substituted or unsubstituted aromatic divalent group, an oxypoly (dimethylsiloxy) group or oxygen,

or by the following formula (5):

$$\begin{array}{c|c}
 & R^6 \\
 & Si - O \\
 & H \\
 & n
\end{array}$$
(5)

where R⁶ represents alkyl, aryl, aralkyl or hydrogen, and n represents an integer of 2 or greater.

13. (Original) A borazine-based resin composition comprising a polymer with a borazine skeleton on a main chain or a side chain thereof, and a solvent capable of dissolving the polymer, and having a solid concentration of 0.5 wt% or greater and a metal impurity content of no greater than 30 ppm.

14. (Currently Amended) A borazine-based resin composition-according to-claim-13 comprising a polymer with a borazine skeleton on a main chain or a side chain thereof, and a solvent capable of dissolving the polymer, and having a solid concentration of 0.5 wt% or greater and a metal impurity content of no greater than 30 ppm, wherein the polymer is a borazine-based resin produced by a borazine-based resin production process according to any one of claims 8 to 12 claim 8.

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15. (Currently Amended) A borazine-based resin composition according to claims 13 or 14 claim 13,

wherein the polymer has a repeating unit represented by the following formula (2):

$$Z^{1} = -\frac{R^{3}}{R^{4}} - \frac{R^{5}}{R^{4}} - \frac{R^{3}}{R^{4}} - \frac{R^{3}}{R^{4}} - \frac{R^{5}}{R^{4}} - \frac{R^{5}}{R^{5}} - \frac$$

where

R¹ represents alkyl, aryl, aralkyl or hydrogen,

R² represents alkyl, aryl, aralkyl or hydrogen,

R³ and R⁴ represent identical or different monovalent groups selected from among alkyl, aryl, aralkyl and hydrogen,

R⁵ represents a substituted or unsubstituted aromatic divalent group, an oxypoly(dimethylsiloxy) group or oxygen,

R⁶ represents alkyl, aryl, aralkyl or hydrogen,

a represents a positive integer, b represents 0 or a positive integer, p represents 0 or a positive integer, and q represents 0 or a positive integer.

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16. (Currently Amended) A method for forming an insulating film on a substrate,

wherein a borazine-based resin composition according to any one of claims 13 to 15 claim 13 is coated onto the substrate to form a coated film, and the coated film is then dried.

- 17. (Original) An insulating film provided on a substrate, the insulating film being formed by a method for forming an insulating film according to claim 16.
 - 18. (Original) An insulating film according to claim 17,

wherein the insulating film is formed between mutually adjacent conductive layers among a plurality of conductive layers provided on the substrate.

- 19. (Currently Amended) An electronic part comprising an insulating film according to claim 17-or 18.
- 20. A borazine-based resin produced by a borazine-based resin production process according to any one of claims 8 to 12claim 8.